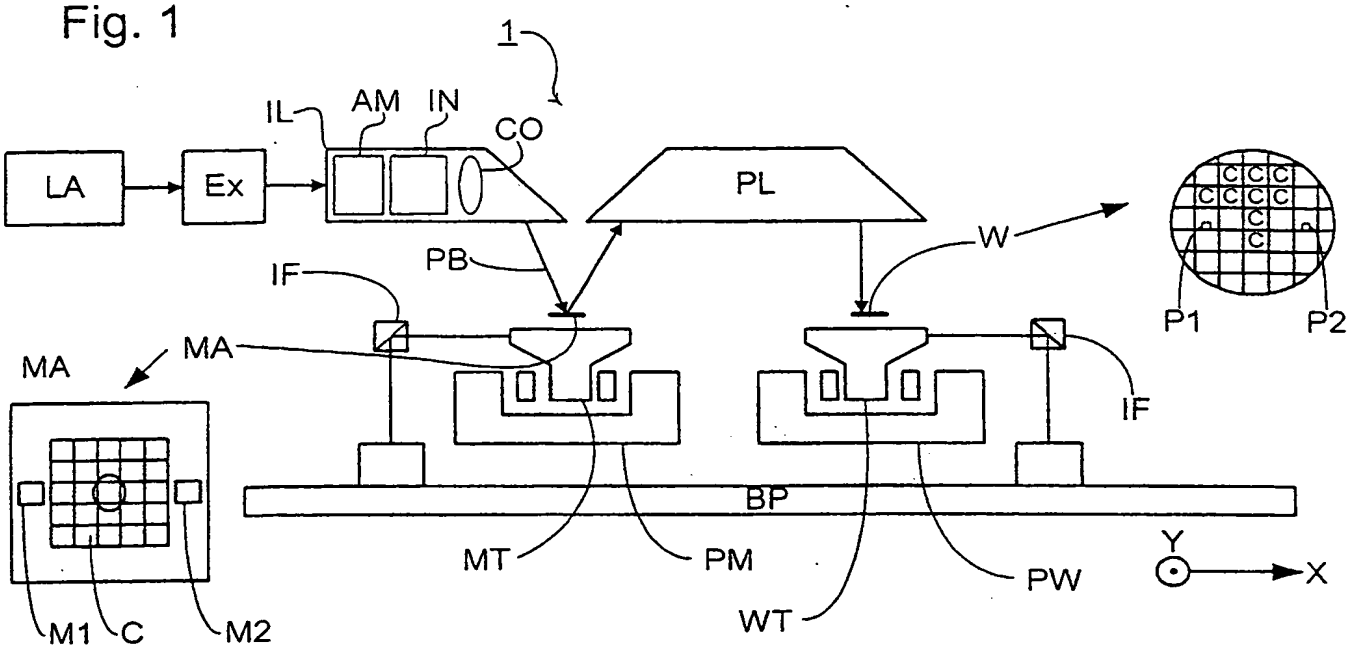
Fig. 1



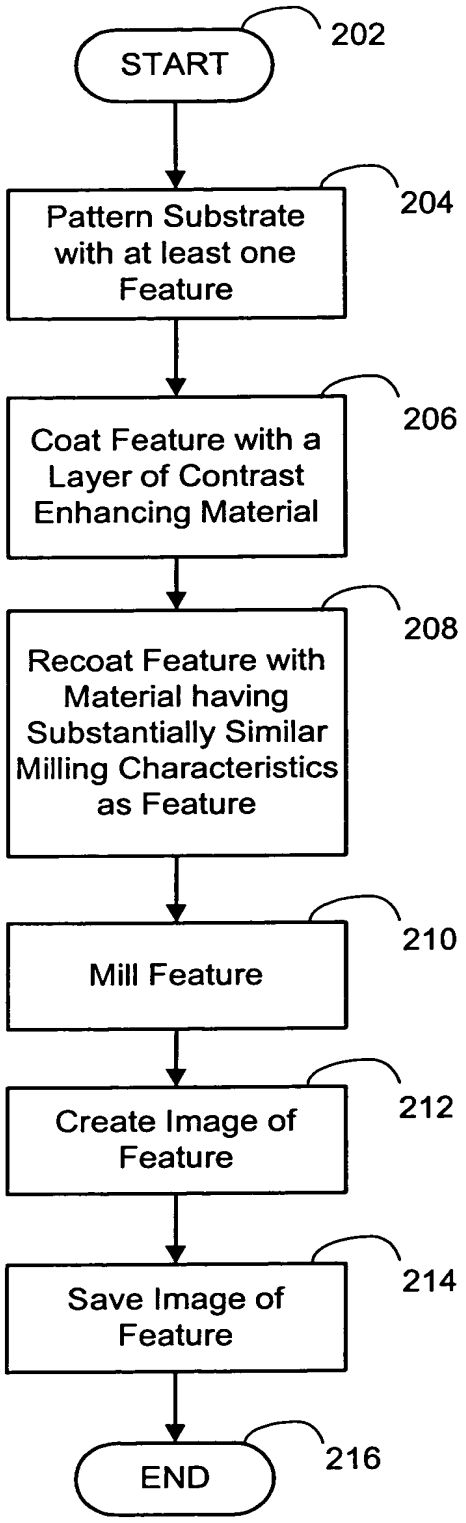

200
START
202
Pattern Substrate with at least one Feature
204
Coat Feature with a Layer of Contrast Enhancing Material
206
Recoat Feature with Material having Substantially Similar Milling Characteristics as Feature
208
Mill Feature
210
Create Image of Feature
212
Save Image of Feature
214
END
216

FIG. 2

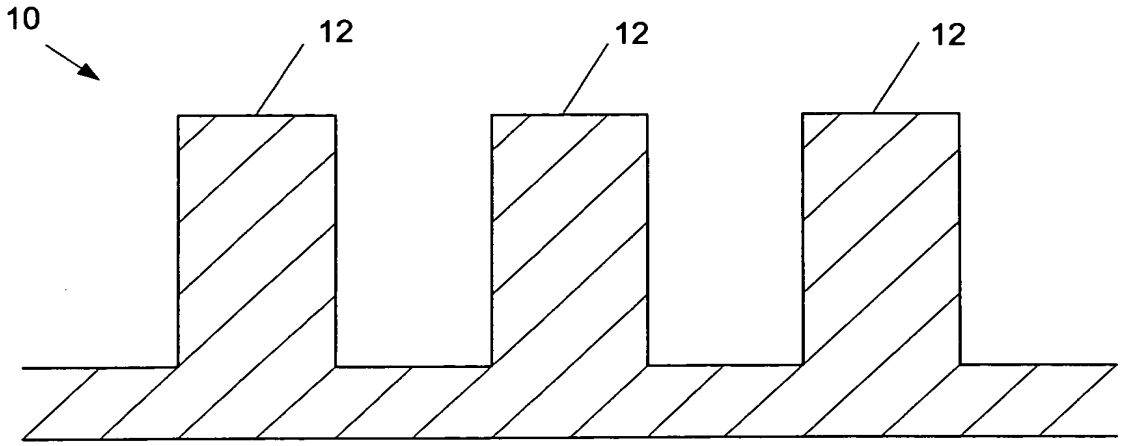


FIG. 3

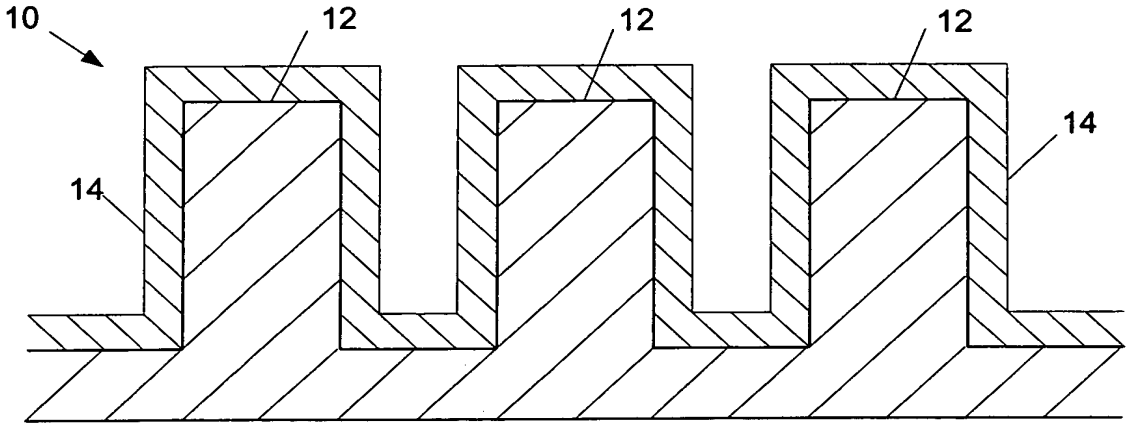


FIG. 4

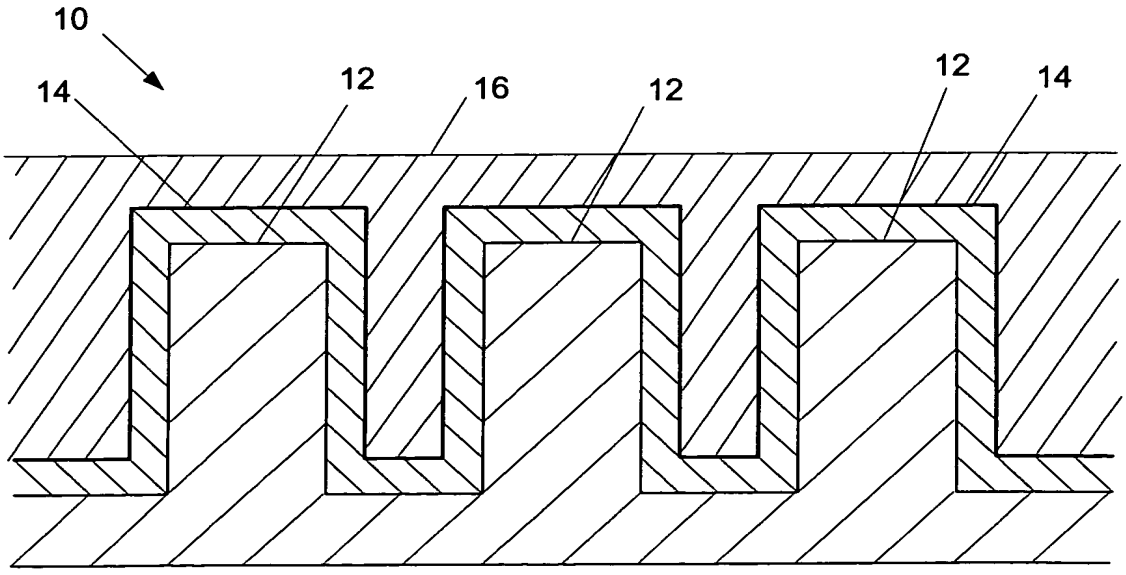


FIG. 5

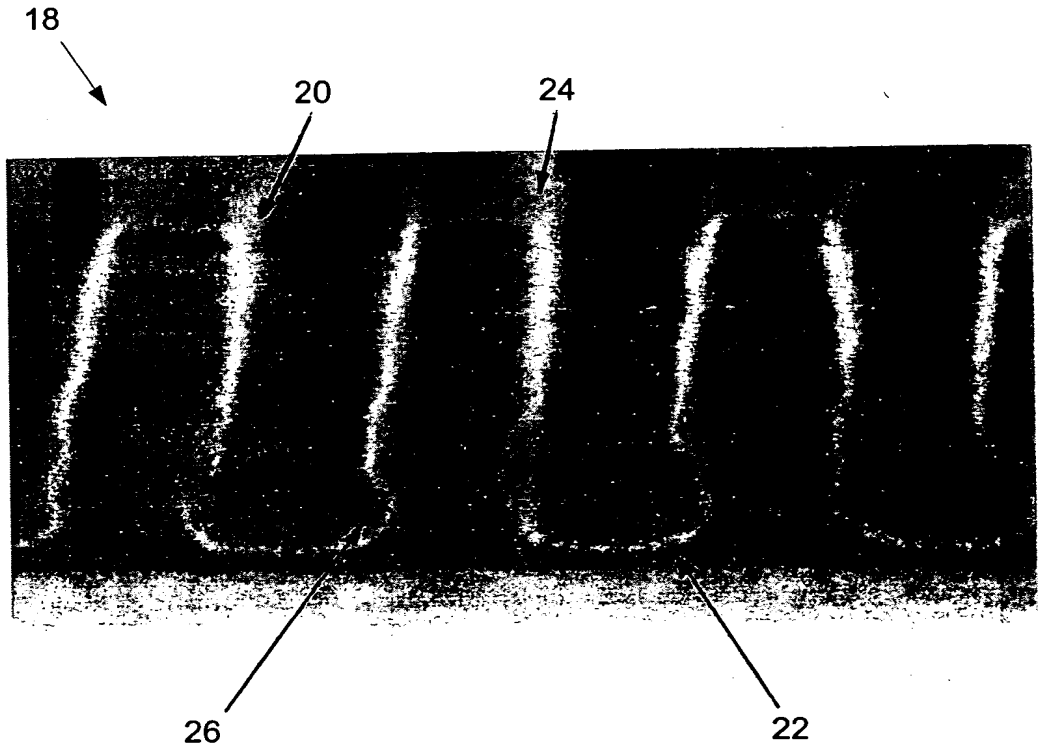


FIG. 6

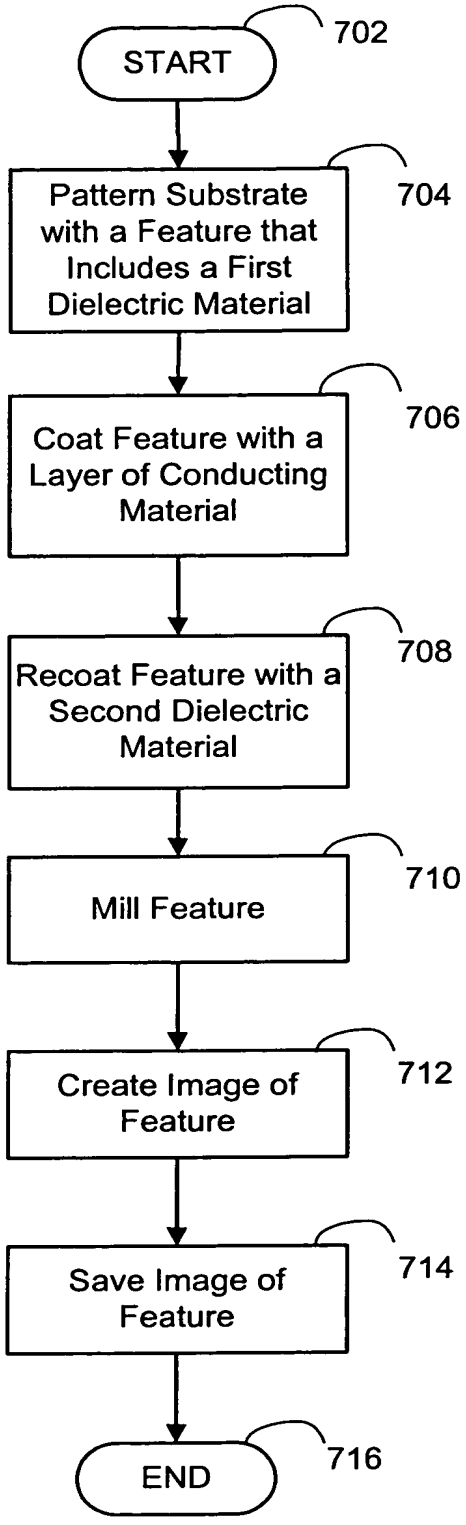

700
START
702
Pattern Substrate with a Feature that Includes a First Dielectric Material
704
Coat Feature with a Layer of Conducting Material
706
Recoat Feature with a Second Dielectric Material
708
Mill Feature
710
Create Image of Feature
712
Save Image of Feature
714
END
716

FIG. 7

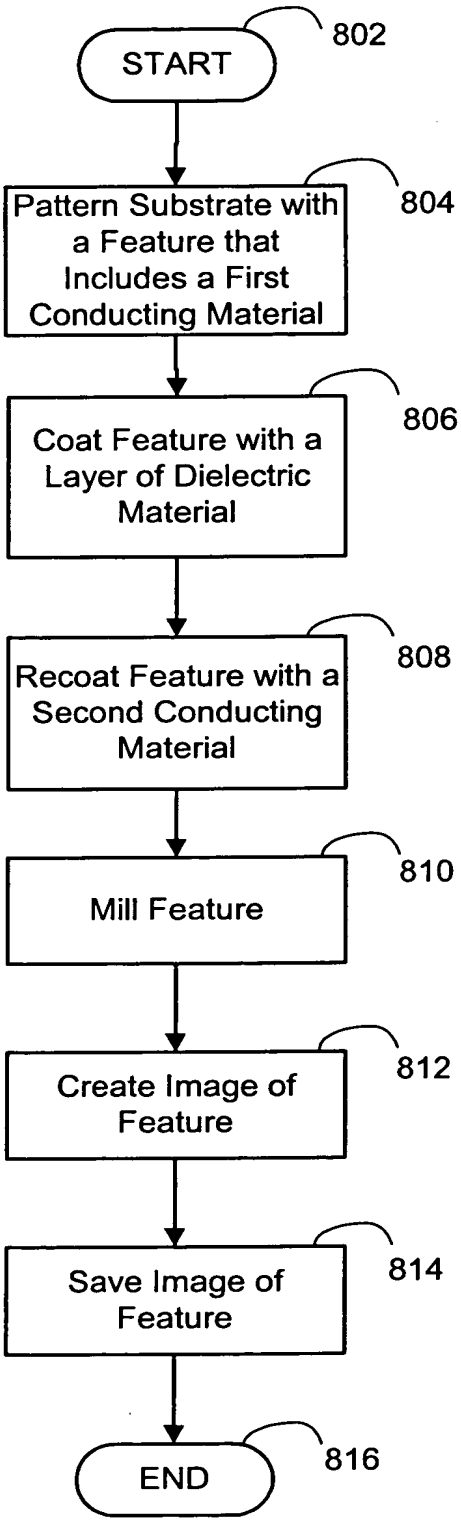

800
802
START
804
Pattern Substrate with a Feature that Includes a First Conducting Material
806
Coat Feature with a Layer of Dielectric Material
808
Recoat Feature with a Second Conducting Material
810
Mill Feature
812
Create Image of Feature
814
Save Image of Feature
816
END

FIG. 8

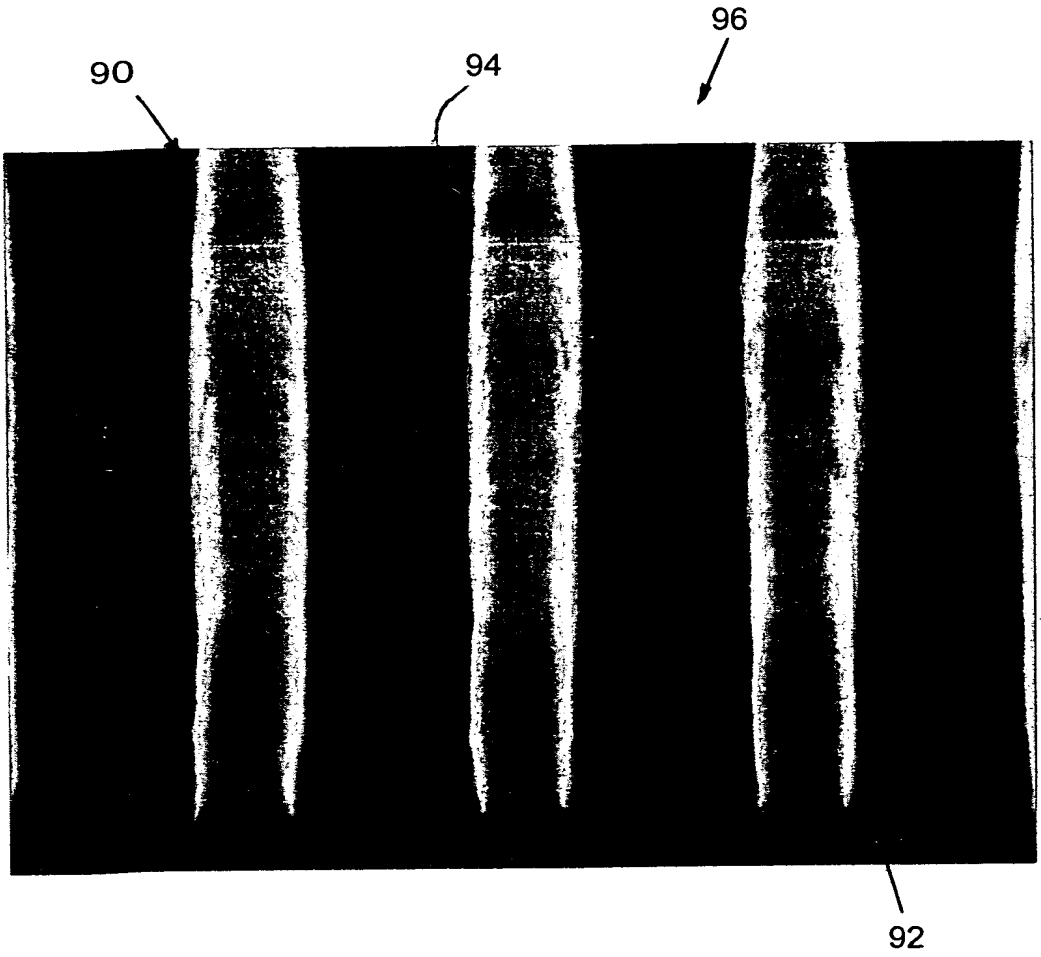


FIG. 9
(RELATED ART)